

# Optimization of AlTiBN coatings deposited by HiPIMS

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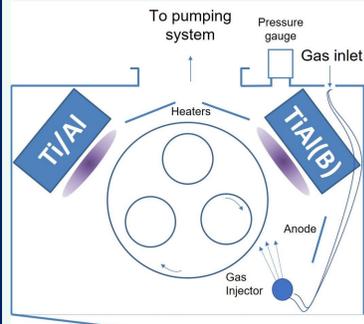
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## MOTIVATION

- Hard nitride (Ti, Al)N-based coatings deposited by magnetron sputtering (MS) suffer from limited thermal stability and fracture toughness.
- HiPIMS method offer higher energetic deposition conditions.
- AlTiBN and AlTiN coatings were deposited by HiPIMS to study the effect of Al content and B doping. AlTiBN also deposited by DCMS for comparison with HiPIMS.
- Al<sub>x</sub>Ti<sub>1-x</sub>(B)N deposited with x ratios between 0.50 and 0.80.

**Aim:** Produce harder and tougher AlTiBN coatings suitable for high temperature applications.

## COATINGS DEPOSITION SETUP AND COMPOSITIONS

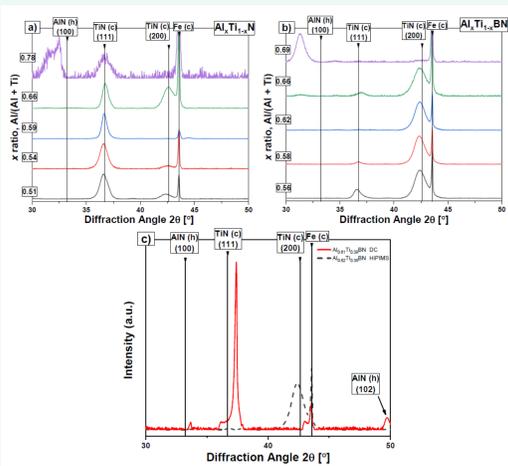


Industrial-scale deposition setup.

Coating	Targets	Power	Composition (at.%)				x	Thickness (µm)	Deposition Rate (µm/h)
			Al	Ti	B	N			
AlTiN-1	Al <sub>50</sub> Ti <sub>50</sub> + Ti	3kW and 0.5kW	24.40	23.80	—	51.73	0.51	2.45	0.98
AlTiN-2	Al <sub>50</sub> Ti <sub>50</sub>	3kW	25.79	21.85	—	52.27	0.54	1.99	0.80
AlTiN-3	Al <sub>50</sub> Ti <sub>50</sub> + Al	3kW and 0.25kW	26.79	18.67	—	54.55	0.59	1.59	0.64
AlTiN-4	Al <sub>50</sub> Ti <sub>50</sub> + Al	3kW and 0.5kW	29.36	14.98	—	55.39	0.66	1.69	0.68
AlTiN-5	Al <sub>50</sub> Ti <sub>50</sub> + Al	3kW and 2.0kW	34.61	9.80	—	55.25	0.78	2.75	1.1
AlTiBN-1	Al <sub>55</sub> Ti <sub>35</sub> B <sub>10</sub> + Ti	3kW and 2.0kW	25.35	20.12	0.85	53.43	0.56	2.66	1.33
AlTiBN-2	Al <sub>55</sub> Ti <sub>35</sub> B <sub>10</sub> + Ti	3kW and 1.5kW	26.69	19.35	0.91	52.35	0.58	2.01	1.01
AlTiBN-3	Al <sub>55</sub> Ti <sub>35</sub> B <sub>10</sub> + Ti	3kW and 1.0kW	28.44	17.50	0.97	52.58	0.62	1.80	0.90
AlTiBN-4	Al <sub>55</sub> Ti <sub>35</sub> B <sub>10</sub> + Ti	3kW and 0.5kW	30.36	15.68	1.10	52.55	0.66	1.67	0.84
AlTiBN-5	Al <sub>55</sub> Ti <sub>35</sub> B <sub>10</sub>	3kW	31.31	14.18	1.19	53.31	0.69	1.59	0.80
AlTiBN DC	Al <sub>55</sub> Ti <sub>35</sub> B <sub>10</sub> + Ti	3kW and 1.0kW	27.87	17.67	3.68	50.01	0.61	3.51	1.76

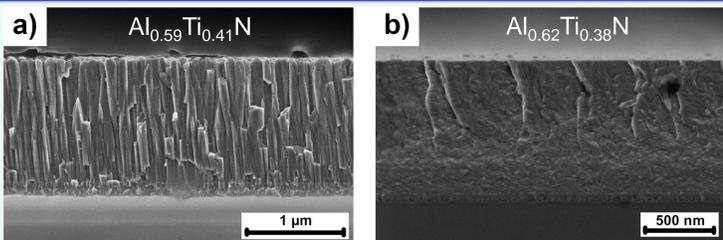
Deposition procedure and composition results extracted from GDOES analysis.

## XRD



a) Al<sub>x</sub>Ti<sub>1-x</sub>N HiPIMS, b) Al<sub>x</sub>Ti<sub>1-x</sub>BN HiPIMS and c) Al<sub>x</sub>Ti<sub>1-x</sub>BN DCMS (c) XRD spectra.

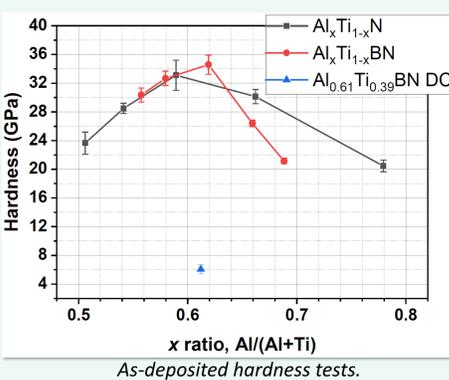
## SEM



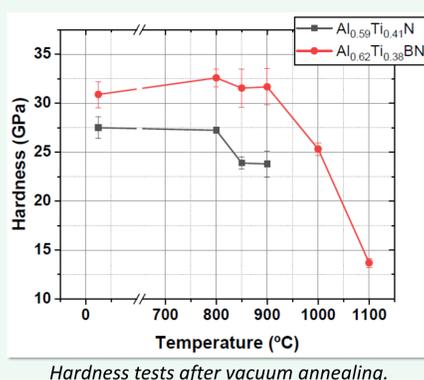
Al<sub>0.59</sub>Ti<sub>0.41</sub>N shows a columnar structure.

Al<sub>0.62</sub>Ti<sub>0.38</sub>BN shows a fine-grained structure.

## Nanoindentation



As-deposited hardness tests.



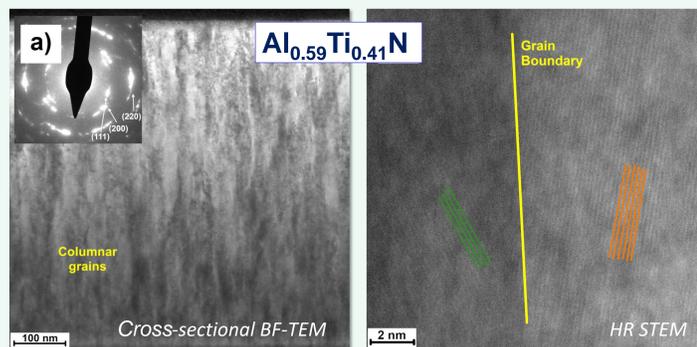
Hardness tests after vacuum annealing.

- Al<sub>x</sub>Ti<sub>1-x</sub>(B)N with x ≈ 0.6 offer the highest hardness.
- Higher H/E and H<sup>3</sup>/E<sup>2</sup> ratios for Al<sub>x</sub>Ti<sub>1-x</sub>BN suggest ↑ fracture toughness.
- Al<sub>0.62</sub>B<sub>0.38</sub>BN offers improved thermal stability (up to 1100 °C).

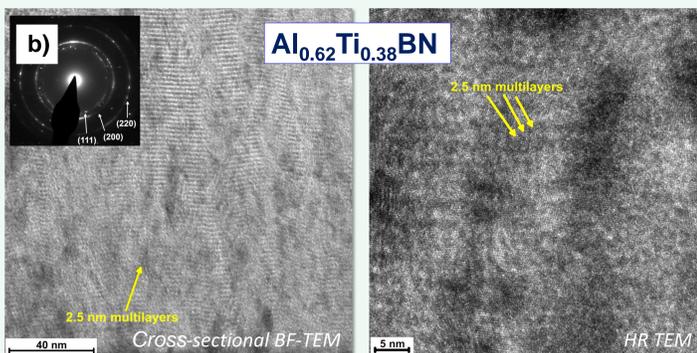
## PROPERTIES

- Coatings up to x = 0.6 present a predominant fcc-cubic structure.
- B-doping, in combination with HiPIMS energetic bombardment, promotes (200) orientation over (111).
- At high x ratios and low-energy bombardment (DCMS), the detrimental hex-AlN phase appears.

## TEM



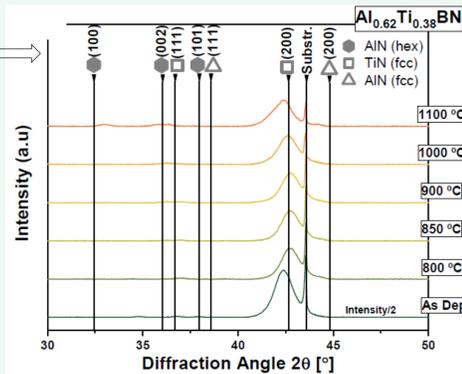
- Dense columnar structure of ~20 nm wide grains oriented in the growth direction.
- Lattice planes extend continuously within the columnar grains and are interrupted by the grain boundary showing high degree of crystallinity.



- Multilayer pattern resulted from substrate rotation during co-sputtering and the presence of B.
- B-addition triggered the formation of a more nanocrystalline structure.
- ≈14 at. % B (from EELS).

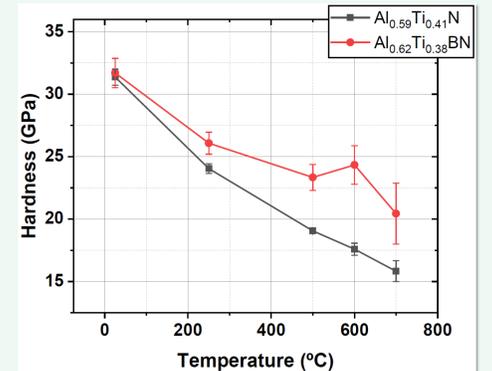
➤ HiPIMS and B doping results in a dense **nanocomposite microstructure** composed of nanocrystalline Ti(Al)N domains (≈ 2 nm) and amorphous regions [Ti(Al)B<sub>2</sub> and BN].

## XRD (After vacuum annealing)



- Formation onset of detrimental h-AlN delayed from 850 °C for Al<sub>0.59</sub>Ti<sub>0.41</sub>N to 1100 °C for Al<sub>0.62</sub>B<sub>0.38</sub>BN.

## Hot hardness



- Superior hot hardness for Al<sub>0.62</sub>B<sub>0.38</sub>BN up to 750 °C ⇒ better performance for high temperature applications.

## FURTHER INFORMATION

- A. Mendez et al. Surface & Coatings Technology 422 (2021) 127513 <https://doi.org/10.1016/j.surfcoat.2021.127513>

## ACKNOWLEDGEMENTS

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